

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Lichun Liegh Chen eta l.
Serial No.: TBD
Filing Date: Herewith
Title: IN-SITU DIFFUSION ALLOYING AND PRE-OXIDATION ANNEALING IN AIR
OF FeCrAl ALLOY CATALYTIC CONVERTER MATERIAL
Docket No.: 35296

INFORMATION DISCLOSURE STATEMENT

Mail Stop PATENT APPLICATION
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Applicants are aware of the publications listed in the enclosed copy of Patent Office Form 1449.

In accordance with the notification issued by the Office of Patent Legal Administration dated June 17, 2003, the requirement to submit the cited U.S. references is waived as the above-referenced application is being filed after June 30, 2003. Copies of cited foreign references are enclosed.

Respectfully submitted,

PEARNE & GORDON LLP

By:



Brian G. Bembenick, Reg. No. 41463

1801 East 9th Street
Suite 1200
Cleveland, Ohio 44114-3108
(216) 579-1700

Date: March 24, 2004

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INFORMATION DISCLOSURE CITATION
BY APPLICANT
(USE SEVERAL SHEETS IF NECESSARY)

Page 1 of 1

APPLICANT:
Lichun Leigh Chen et al.FILING DATE:
HerewithGROUP ART UNIT:
TBD

U.S. PATENT DOCUMENTS

Examiner Initial		Document No.	Date	Name	Class	Subclass	Filing Date
	A	3,394,659	7/1968	Van Alen			
	B	3,907,611	9/1975	Sasame et al.			
	C	4,079,157	3/1978	Yagi et al.			
	D	4,228,203	10/1980	Yagi et al.			
	E	5,366,139	11/1994	Jha et al.			
	F	5,447,698	9/1995	Jha et al.			
	G						
	H						
	I						
	J						
	K						
	L						

FOREIGN PATENT DOCUMENTS

		Document No.	Date	Country	Class	Subclass	Translation
	M	0 475 420	3/1992	EP			Cited on pg 1 of Spec. as EP Appl. 91115501.8
	N						
	P						
	Q						

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

	R	
	S	
	T	

Examiner: _____ Date Considered _____

*Examiner: Initial if reference considered, regardless of whether citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.